

# Synthesis and Characterization of Ni-Pt Alloy Thin Films Prepared by Supercritical Fluid Chemical Deposition Technique

Sudiyarmanto <sup>1,2</sup>, and Eiichi Kondoh <sup>1,\*</sup>

<sup>1</sup> Integrated Graduate School of Medicine, Engineering, and Agricultural Sciences, University of Yamanashi, Kofu, 400-8511, Japan; g18dtea3@yamanashi.ac.jp

<sup>2</sup> Research Center for Chemistry, Indonesian Institute of Sciences (LIPI), Kawasan PUSPIPTEK Serpong, Tangerang Selatan, Banten, 15310, Indonesia; sudi012@lipi.go.id

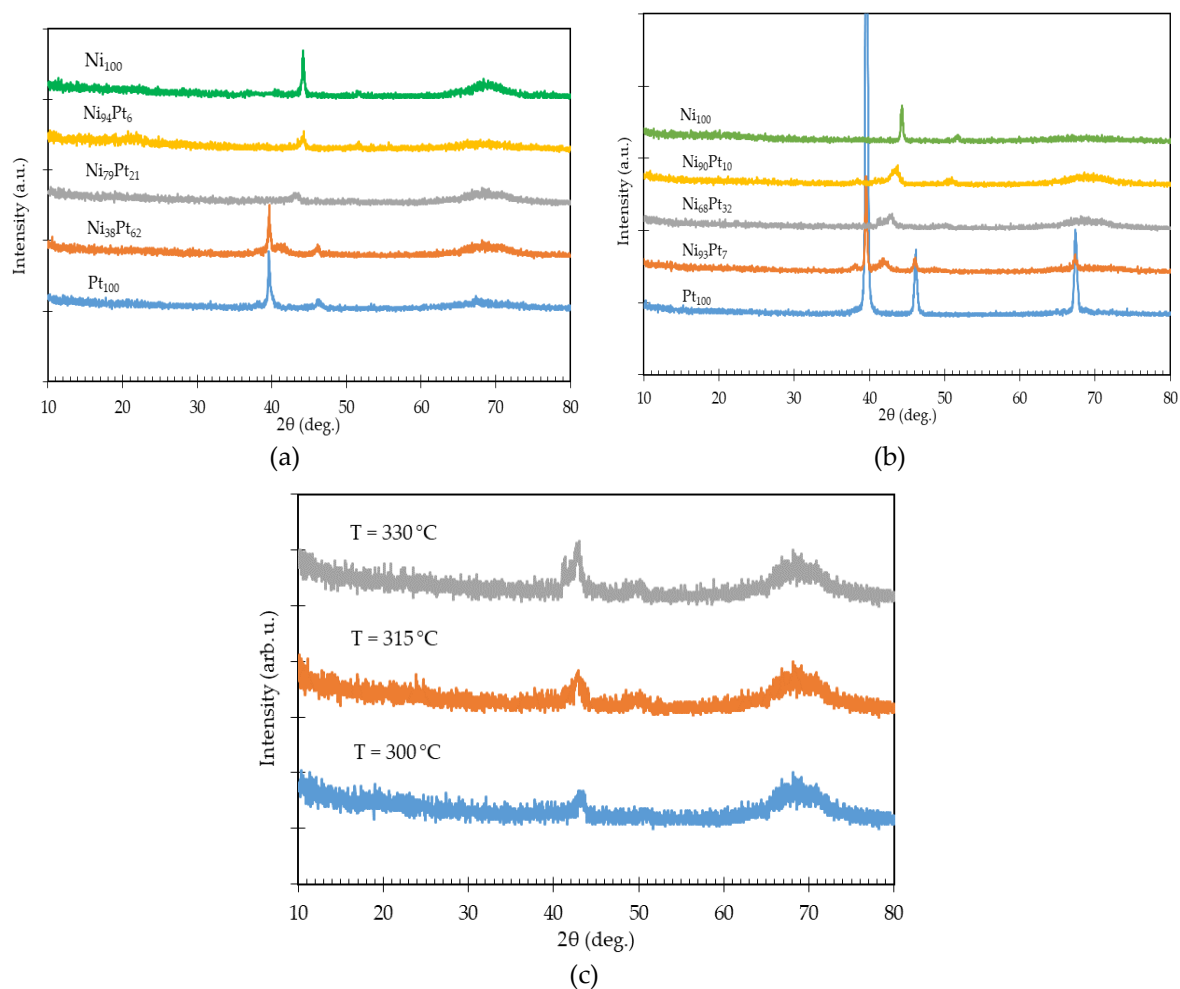
\* Correspondence: kondoh@yamanashi.ac.jp; Tel.: +81-55-220-8472

## 1. Thickness measurement for Ni-Pt alloy thin films

**Table S1.** Thickness measurement for Ni-Pt alloy thin films

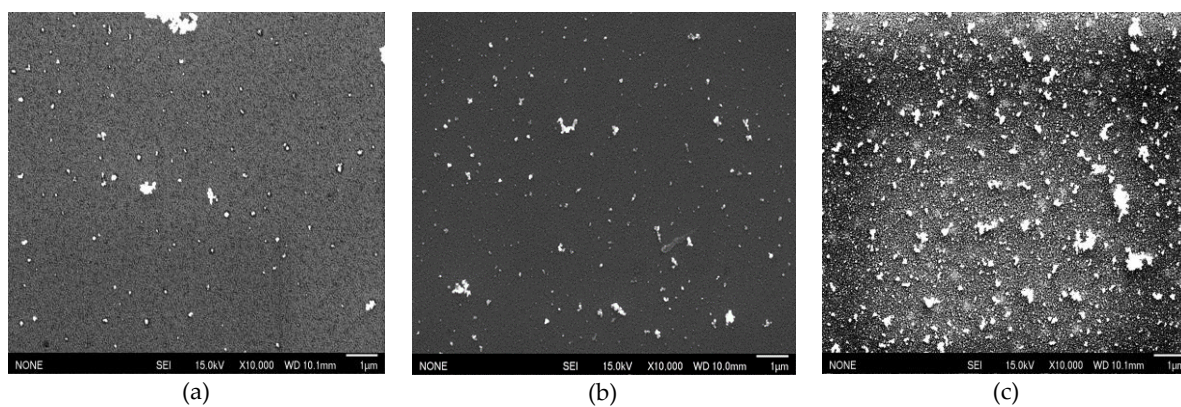
| Sample name                       | Thickness (nm) |            |            |
|-----------------------------------|----------------|------------|------------|
|                                   | T = 300 °C     | T = 315 °C | T = 330 °C |
| Pt <sub>100</sub>                 | 259.26         | 291.66     | 320.27     |
| Ni <sub>20</sub> Pt <sub>80</sub> | 252.60         | 282.60     | 304.25     |
| Ni <sub>50</sub> Pt <sub>50</sub> | 234.28         | 250.55     | 259.26     |
| Ni <sub>80</sub> Pt <sub>20</sub> | 200.64         | 223.90     | 231.38     |
| Ni <sub>100</sub>                 | 188.71         | 169.50     | 162.66     |

## 2. XRD patterns



**Figure S1.** XRD patterns for deposited Ni-Pt alloy thin films at different elemental compositions: (a) T = 300 °C; (b) T = 330 °C; (c) Ni/Pt with precursor ratio of 50:50 (at.%) at different temperatures

## 3. SEM images



**Figure S2.** SEM images of deposited Ni-Pt alloy thin films at temperature of 300 °C: (a) Ni<sub>94</sub>Pt<sub>6</sub>; (b) Ni<sub>79</sub>Pt<sub>21</sub>; (c) Ni<sub>38</sub>Pt<sub>62</sub>